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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/518,532	12/30/2004	Jean-Philippe Borgoltz	263673US2XPCT	9528	
OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET			EXAMINER		
			ELVE, MARIA ALEXANDRA		
ALEXANDRIA, VA 22314			ART UNIT	PAPER NUMBER	
			1725		
			NOTIFICATION DATE	DELIVERY MODE	
·			06/06/2007	ELECTRONIC	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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		Application No.	Applicant(s)
		10/518,532	BORGOLTZ ET AL.
Office Action Summary		Examiner	Art Unit
		M. Alexandra Elve	1725
The MA Period for Reply	AILING DATE of this communication app	ears on the cover sheet with the	correspondence address
WHICHEVER - Extensions of time after SIX (6) MON - If NO period for re - Failure to reply we Any reply receive	ED STATUTORY PERIOD FOR REPLY IS LONGER, FROM THE MAILING DATE of any be available under the provisions of 37 CFR 1.13 THS from the mailing date of this communication. Supply is specified above, the maximum statutory period within the set or extended period for reply will, by statute, do by the Office later than three months after the mailing madjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATIO 36(a). In no event, however, may a reply be to till apply and will expire SIX (6) MONTHS fron cause the application to become ABANDON	N. mely filed n the mailing date of this communication. ED (35 U.S.C. § 133).
Status			
2a) ☐ This acti 3) ☐ Since th	sive to communication(s) filed on <u>30 De</u> ion is FINAL . 2b)⊠ This is application is in condition for allowar n accordance with the practice under <i>E</i>	action is non-final. nce except for formal matters, pr	
Disposition of Cl	aims		
4a) Of th 5) ☐ Claim(s) 6) ☑ Claim(s) 7) ☐ Claim(s)	a 11-20 is/are pending in the application e above claim(s) is/are withdrav is/are allowed. a 11-20 is/are allowed. b 11-20 is/are rejected. c is/are objected to. are subject to restriction and/or	vn from consideration.	
Application Pape	ers		
10)⊠ The draw Applicant Replacer	cification is objected to by the Examine ving(s) filed on <u>30 December 2004</u> is/at may not request that any objection to the connect drawing sheet(s) including the correct or declaration is objected to by the Ex	re: a)⊠ accepted or b)⊡ object drawing(s) be held in abeyance. Se ion is required if the drawing(s) is ol	ee 37 CFR 1.85(a). bjected to. See 37 CFR 1.121(d).
Priority under 35	U.S.C. § 119		
a)⊠ All b 1.⊠ Co 2.□ Co 3.□ Co ap	edgment is made of a claim for foreign O Some * c) None of: ertified copies of the priority documents ertified copies of the priority documents opies of the certified copies of the prior oplication from the International Bureau ttached detailed Office action for a list	s have been received. s have been received in Applica ity documents have been receiv (PCT Rule 17.2(a)).	tion No red in this National Stage
	person's Patent Drawing Review (PTO-948) closure Statement(s) (PTO/SB/08)	4) Interview Summar Paper No(s)/Mail D 5) Notice of Informal 6) Other:	Date

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 11-15 & 17-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Brodsky et al. (USPN 6,489,985) in view of Tomita et al. (USPN 5,369,493).

Brodsky et al. discloses a laser marking system and method. YAG (1064 nm) and CO₂ lasers may be used. A computer(s) controls the X and Y galvanometer mirror devices. These are fast recovery galvanometer mirrors. Mirrors have a wide range of motion and have the ability to be removed (retracted) from the system. The optical output beam from the laser source is collimated and then focused by the respective spherical type of lenses of lens set for directing the beam. The workpiece may be positioned on a conveyor system, which moves a series of workpieces. The working field of the scanner at the image plane may be a square or rectangular that may be varied in size on a side from about 60 nm to about 180 nm depending on the chosen flat field lens.

Brodsky et al. does not teach the use of narrow and wide field cameras.

Tomita et al. discloses an apparatus for transporting electronic components.

Imaging and moving the components, requires the use of a wide and narrow field camera. The cameras may be use to check position of components of differing size.

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The narrow field camera detects small components and the wide field detects large components.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use both a wide and a narrow field camera, as taught by Tomita et al. in the Brodsky et al. system because it ensures that all workpieces are properly observed and processed.

Claim 16 is rejected under 35 U.S.C. 103(a) as being unpatentable over Brodsky et al. and Tomita et al., as stated above and further in view of Chiba et al. (USPAP 2001/0014543A1).

Brodsky et al. and Tomita et al. do not teach the use of reactive gas.

Chiba et al. discloses a semiconductor wafer laser marking system. One of the processing steps involves the use of a reactive gas mixture to enhance crystalline growth on the wafer.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use reactive gas, as taught by Chiba et al. in the Brodsky et al. and Tomita et al. system because it is a standard wafer processing step.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to M. Alexandra Elve whose telephone number is 571-272-1173. The examiner can normally be reached on 6:30-3:00 Monday to Friday.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Patrick J. Ryan can be reached on 571-272-1292. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

May 28, 2007.

M. Alexandra Elve

Primary Examiner 1725